

SUBSTRATE PROCESSING SYSTEM AND SUBSTRATE ABNORMALITY DETECTION METHOD

ABSTRACT

This substrate processing system includes a load port, a processing chamber, a measurer, and a controller. The load port is configured such that a storage container containing a substrate can be connected thereto. The processing chamber is configured to implement substrate processing on the substrate. The measurer is provided on a path for transporting the substrate between the storage container and the processing chamber, and is configured to measure an in-plane spectral distribution of the substrate. The controller is configured to create an outlier detection model on the basis of the in-plane spectral distribution of the substrate measured by the measurer, use the created outlier detection model to calculate an in-plane score of the substrate from the measured in-plane spectral distribution of the substrate, and detect abnormality in the substrate on the basis of the calculated score.

Fig. 3